



Patent Application No. 10/687,424
Customer No. 42717

IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Jhon Jhy Liaw	§	Docket No.:	24061.39 / 2003-0030
Serial No.:	10/687,424	§	Examiner:	Kin Chan Chen
Filing Date:	October 16, 2003	§	Art Unit:	1765
For:	Process Integration of SOI FETs With Active Layer Spacer	§	Conf. No.:	8019

RESPONSE UNDER EX PARTE QUAYLE ACTION

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed on May 23, 2005, please enter the amendment herein to correct defects as to formal matters.

Amendments to the Claims are reflected in the listing of claims, which begins on page 2 of this paper.

Remarks begin on page 4 of this paper.